



Plasma Oxidation and Reduction of Nitrogen: Towards Electrification of Nitrogen Fixation

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Message from the Guest Editor

The naturally occurring N_2 fixation is becoming negligible compared to the ever-growing global demand, while the chemical production of NH_3 alone reaches hundreds of millions of tonnes, predominantly by the Haber-Bosch process, which relies heavily on fossil-derived energy and massively contributes to the total global CO_2 emissions. Naturally, new, more benign routes of N_2 fixation are under investigation. Among these are the processes involving plasma. This vast interest in plasma-assisted and plasma-driven methods is due to their operation under benign conditions, which complies with the desired electrification of chemical industry, leading towards a more sustainable future.

We are honoured to announce this Special Issue of *Applied Sciences*. We cordially invite authors to contribute their works, which we expect to be focussed on all aspects of N_2 fixation by plasma, including experimental and computational research in areas of plasma chemistry, physics, biomedicine, catalysis, diagnostics, etc.

Keywords

- Nitrogen fixation
- Plasma chemistry
- Plasma catalysis
- Plasma physics
- Plasma diagnostics
- Ammonia
- Nitrogen oxide





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Message from the Editor-in-Chief

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